KLA is an industry-leading supplier of etch and deposition equipment for the manufacturing of compound semiconductor devices for RF, power and optoelectronic applications.

We offer production-proven processes:

- 8 of the Top 10 III-V IDMs use SPTS systems
- 4 of the Top 5 III-V foundries use SPTS systems
- 2 of the Top 5 HB-LED IDMs use SPTS systems

Our global network of sales and service offices provides world-class local support to all our customers throughout Asia, North America and Europe.

Typical applications of KLA’s processes include high rate backside via etch, low damage frontside etch, high aspect ratio silicon trench etch, and deposition of metal or dielectric layers for stress control, electrical contacts, via seed layers, passivation or anti-reflective coatings.

KLA is a key partner in CSconnected, the world’s first compound semiconductor cluster, which represents organisations associated with research, development and manufacturing of compound semiconductors, with the aim to promote collaborative development for the advancement of compound semiconductor expertise, technologies and products.

**KLA PRODUCTS**

**SPTS Omega® ICP**
Module for etching a wide variety of compound semiconductor materials, such as GaAs, InP, SiNx, and GaN.

**SPTS Omega® Synapse**
Module with 10x ion density of ICP, designed to etch strongly bonded materials such as SiC, GaN and sapphire.

**SPTS Omega® DSi-v / Rapier**
Established high rate silicon DRIE modules with unique end-point solutions.

**SPTS Delta™ PECVD**
Deposition of low damage, stress-controlled SiOx and SiN layers with unparalleled uniformity and deposition temperatures <250°C.

**SPTS Sigma® PVD**
High productivity metal layer deposition, with excellent film uniformity, for frontside and backside applications.
**ETCH PROCESSES FOR COMPOUND SEMICONDUCTORS**

<table>
<thead>
<tr>
<th>Device Technology</th>
<th>Substrate</th>
<th>Etch Layers</th>
<th>Requirements</th>
</tr>
</thead>
<tbody>
<tr>
<td><strong>RF Devices</strong></td>
<td></td>
<td></td>
<td></td>
</tr>
<tr>
<td>GaAs</td>
<td>GaAs</td>
<td>Mesa, backside via, SiN, BCB/PI</td>
<td>Field proven processes</td>
</tr>
<tr>
<td>InP</td>
<td>InP</td>
<td>InP</td>
<td>High InP via etch rate</td>
</tr>
<tr>
<td>GaN on SiC</td>
<td>SiC</td>
<td>SiC backside via GaN</td>
<td>High rate SiC via GaN base layer</td>
</tr>
<tr>
<td><strong>Power Devices</strong></td>
<td></td>
<td></td>
<td></td>
</tr>
<tr>
<td>GaN on Si</td>
<td>Si</td>
<td>GaN epi Si backside via</td>
<td>Slow, controllable, low damage epi etch High rate Si TSV</td>
</tr>
<tr>
<td>SiC</td>
<td>SiC</td>
<td>Oxide SiC</td>
<td>Profile control No microtrenching</td>
</tr>
<tr>
<td><strong>Optoelectronics</strong></td>
<td></td>
<td></td>
<td></td>
</tr>
<tr>
<td>VCSELs</td>
<td>GaAs</td>
<td>Epi stack SiN</td>
<td>Profile, smoothness, end-point</td>
</tr>
<tr>
<td>High Brightness LEDs</td>
<td>Sapphire, Ge, Si</td>
<td>GaN Oxide</td>
<td>High rate, profile &amp; high MTBC</td>
</tr>
<tr>
<td>InP Communications</td>
<td>InP</td>
<td>InP, InGaAs, InGaAsP</td>
<td>Profile control &amp; smoothness</td>
</tr>
</tbody>
</table>

**DEPOSITION PROCESSES FOR COMPOUND SEMICONDUCTORS**

KLA offers PECVD and PVD deposition process modules which are compatible with handling smaller and often fragile wafers commonly used in the compound semiconductor industry - down to 3” for PECVD and 4” for PVD. Our processes offer films with excellent stress and uniformity control, on reliable, high throughput, production-proven SPTS Sigma® and SPTS Delta™ cluster platforms.

**SPTS Delta™ PECVD**

KLA has the largest PECVD installed base in high volume manufacturing of MIMCAP (metal-insulator-metal capacitors) insulators and other passivation layers in GaAs RF-ICs. Delta™ PECVD offers excellent SiN reliability for MIMCAP insulation with a WIW thickness uniformity 2x better than competing systems. We are also the only supplier to offer remote plasma clean for wafer sizes smaller than 200mm, to increase productivity and reduce chamber damage during cleans.

**SPTS Sigma® PVD**

KLA has a wide range of PVD module technologies to meet the demands of compound RF-IC and MMIC manufacturing. Typical applications include frontside Au interconnects, thin film resistors, backside via seed, RDL/UBM, BAW electrodes & piezoelectric layers, and SAW electrode & encapsulation. Our SPTS Sigma® PVD system includes a unique electrostatic clamp which is compatible with sapphire carriers, without the need for a back-coat of metal.

**KLA SUPPORT**

Maintaining system productivity is an integral part of KLA’s yield optimization solution. Efforts in this area include system maintenance, global supply chain management, cost reduction and obsolescence mitigation, system relocation, performance and productivity enhancements, and certified tool resale.

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